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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

APPL NUM 1G003908	FILING DATE 11/01/2001	CLASS 438	SUBCLASS 216 67	GAU 1765 2812	EXAMINER ALANKO
**APPLICANTS: Entley William; Langan John; Hall Randy; 1765					
**CONTINUING DATA VERIFIED:					
** FOREIGN APPLICATIONS VERIFIED:					
PG-PUB		DO NOT PUBLISH <input checked="" type="checkbox"/>		RESCIND <input type="checkbox"/>	
Foreign priority claimed		<input type="checkbox"/> yes <input type="checkbox"/> no		ATTORNEY DOCKET NO	
35 USC 119 conditions met		<input type="checkbox"/> yes <input type="checkbox"/> no		M-112021 US	
Verified and Acknowledged Examiners's initials					
TITLE : In situ plasma process to remove fluorine residues from the interior surfaces of a CVD reactor <small>U.S. DEPT. OF COMM./PAT. & TM.-PTO-436L(Rev. 12-94)</small>					

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NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for O.G.
ISSUE FEE		DRAWING	
Amount Due	Date Paid	Sheets Drwg.	Figs.Drwg. Print Fig.
		Application Examiner	
<input type="checkbox"/> TERMINAL DISCLAIMER		PREPARED FOR ISSUE	
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